

### **Listing of Claims:**

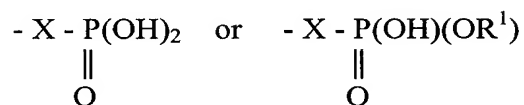
This listing of claims will replace all prior versions, and listings, of claims in the application:

1-23. Cancelled

24 (currently amended). A radiation-sensitive element comprising

- (a) a substrate with at least one hydrophilic surface and
- (b) a radiation-sensitive coating on at least one hydrophilic surface of the substrate, wherein the coating comprises:
  - (i) at least one free-radical polymerizable monomer, oligomer, polymer or mixture thereof with at least one ethylenically unsaturated group each,
  - (ii) at least one photoinitiator or sensitizer, which is capable of absorbing radiation of a wavelength in the range of 250 to 1,200 nm,
  - (iii) at least one stabilizer compound comprising at least one group capable of inhibiting free-radical polymerization, and at least one other group capable of sorption at the hydrophilic surface of the substrate, wherein the stabilizer compound is a monomeric compound, and
  - (iv) optionally at least one additive comprising coinitiators which form free radicals after the excitation of the photoinitiator or sensitizer with radiation of a wavelength of 250 to 1,200 nm, binders, dyes, plasticizers, chain transfer agents, leuco dyes, inorganic fillers, surfactants or polymerization inhibitors not suitable for sorption at the surface of the substrate,

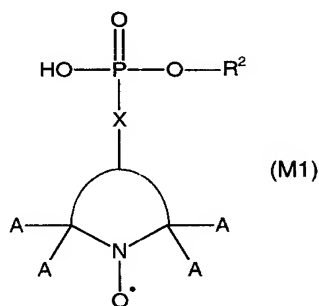
wherein the at least one group of the stabilizer compound capable of sorption at the surface of the substrate is:



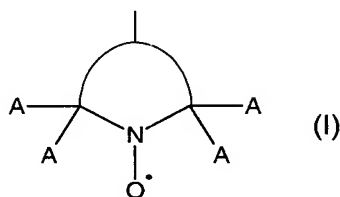
wherein R<sup>1</sup> is C<sub>1</sub>-C<sub>18</sub> alkyl, C<sub>7</sub>-C<sub>11</sub> aralkyl or C<sub>6</sub>-C<sub>10</sub> aryl and X represents a single bond, -O-, -NH- or -N(C<sub>1</sub>-C<sub>10</sub> alkyl)-.

25-28. (cancelled)

29 (currently amended). The radiation-sensitive element according to claim 24 ~~27~~, wherein the monomeric stabilizer compound is represented by formula M1:

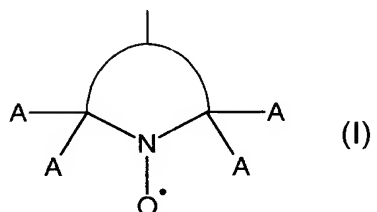


wherein X represents a single bond, -O-, -NH- or -N(C<sub>1</sub>-C<sub>10</sub> alkyl)-, R<sup>2</sup> is hydrogen, C<sub>1</sub>-C<sub>18</sub> alkyl, C<sub>7</sub>-C<sub>11</sub> aralkyl, C<sub>6</sub>-C<sub>10</sub> aryl or a fragment

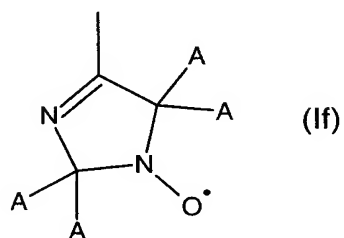
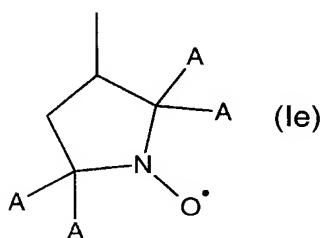
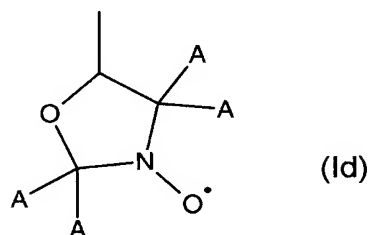
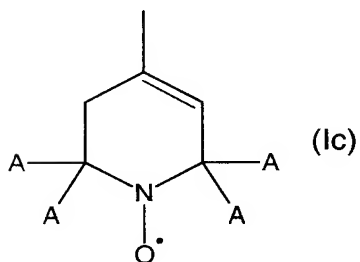
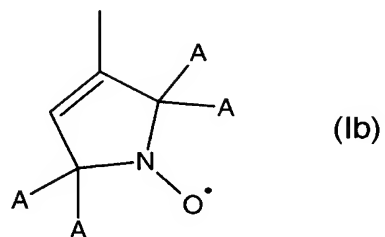
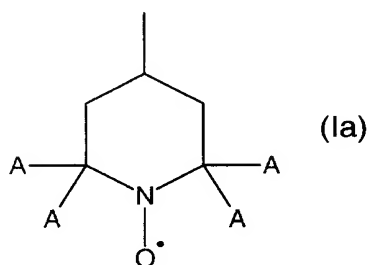


wherein each A is independently optionally substituted C<sub>1</sub>-C<sub>10</sub> alkyl and the nitroxyl function is part of a 5- or 6-membered heterocyclic ring, which optionally comprises one or more double bonds and optionally contains, in addition to the nitrogen atom of the nitroxyl group, one or more O, S or N heteroatoms.

30 (previously presented). The radiation-sensitive element according to claim 29, wherein the fragment



is represented by formulas Ia – If



31 (previously presented). The radiation-sensitive element according to claim 29, wherein X represents  $-O-$ .

32 (previously presented). The radiation-sensitive element according to claim 29, wherein  $R^2$  is a hydrogen atom.

33 (previously presented). The radiation-sensitive element according to claim 29, wherein A is methyl.

34-38. (cancelled)

39 (previously presented). A radiation-sensitive element comprising

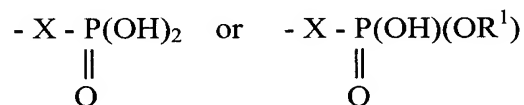
- (a) a substrate with at least one hydrophilic surface and
- (b) a radiation-sensitive coating on at least one hydrophilic surface of the substrate, wherein the coating comprises:
  - (i) at least one free-radical polymerizable monomer, oligomer, polymer or mixture thereof with at least one ethylenically unsaturated group each,
  - (ii) at least one photoinitiator or sensitizer, which is capable of absorbing radiation of a wavelength in the range of 250 to 1,200 nm,
  - (iii) at least one stabilizer compound comprising at least one group capable of inhibiting free-radical polymerization, and at least one other group capable of sorption at the hydrophilic surface of the substrate, and
  - (iv) optionally at least one additive comprising coinitiators which form free radicals after the excitation of the photoinitiator or sensitizer with radiation of a wavelength of 250 to 1,200 nm, binders, dyes, plasticizers, chain transfer agents, leuco dyes, inorganic fillers, surfactants or polymerization inhibitors not suitable for sorption at the surface of the substrate,

wherein the element further comprises an oxygen-impermeable overcoat.

40 (previously presented). A process for the production of a radiation-sensitive element comprising the steps of:

- (a) providing an optionally pretreated substrate having a hydrophilic surface;
- (b) applying to said optionally pretreated substrate having a hydrophilic surface, a radiation-sensitive mixture comprising
  - (i) at least one free-radical polymerizable monomer, oligomer, polymer or mixture thereof with at least one ethylenically unsaturated group each,
  - (ii) at least one photoinitiator or sensitizer, which is capable of absorbing radiation of a wavelength in the range of 250 to 1,200 nm,
  - (iii) at least one stabilizer compound comprising at least one group capable of sorption at the hydrophilic surface of the substrate, and at least one other group capable of inhibiting free-radical polymerization,

wherein the at least one group of the stabilizer compound capable of sorption at the surface of the substrate is:



wherein  $R^1$  is  $C_1$ - $C_{18}$  alkyl,  $C_7$ - $C_{11}$  aralkyl or  $C_6$ - $C_{10}$  aryl and X represents a single bond, -O-, -NH- or -N( $C_1$ - $C_{10}$  alkyl)-,

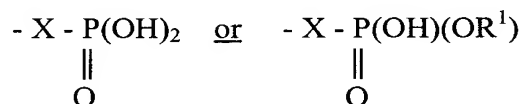
- (iv) a solvent or solvent mixture, and
  - (v) optionally at least one additive comprising coinitiators which form free radicals after the excitation of the photoinitiator or sensitizer with radiation of a wavelength of 250 to 1,200 nm, binders, dyes, plasticizers, chain transfer agents, leuco dyes, inorganic fillers, surfactants or polymerization inhibitors not suitable for sorption at the surface of the substrate;
- and
- c) drying the layer obtained in step (b).

41 (currently amended). A process for the production of a radiation-sensitive element comprising the steps of:

- (a) providing an optionally pretreated substrate having a hydrophilic surface;

- (b) applying to said optionally pretreated substrate having a hydrophilic surface, a mixture that is not radiation-sensitive comprising at least one solvent and at least one stabilizer compound comprising at least one group capable of sorption at the substrate and at least one group capable of inhibiting free-radical polymerization;

wherein the at least one group of the stabilizer compound capable of sorption at the surface of the substrate is:



wherein R<sup>1</sup> is C<sub>1</sub>-C<sub>18</sub> alkyl, C<sub>7</sub>-C<sub>11</sub> aralkyl or C<sub>6</sub>-C<sub>10</sub> aryl and X represents a single bond, -O-, -NH- or -N(C<sub>1</sub>-C<sub>10</sub> alkyl)-,

- (c) drying the layer obtained in step (b);
- (d) applying to the dried layer obtained in step (c), a radiation-sensitive mixture comprising
- (i) at least one free-radical polymerizable monomer, oligomer, polymer or mixture thereof with at least one ethylenically unsaturated group,
  - (ii) at least one photoinitiator or sensitizer, which is capable of absorbing radiation of a wavelength in the range of 250 to 1,200 nm,
  - (iii) a solvent or solvent mixture, and
  - (iv) optionally at least one additive comprising coinitiators which form free radicals after the excitation of the photoinitiator or sensitizer with radiation of a wavelength of 250 to 1,200 nm, binders, dyes, plasticizers, chain transfer agents, leuco dyes, inorganic fillers, surfactants or polymerization inhibitors not suitable for sorption at the surface of the substrate;
- and
- (e) drying the layer obtained in step (d).

42 (previously presented). The process according to claim 40, wherein the process further comprises the step of applying an oxygen-impermeable overcoat to the layer dried in step (c).

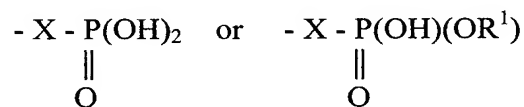
43 (previously presented). The process according to claim 41, wherein the process further comprises the step of applying an oxygen-impermeable overcoat to the layer dried in step (e).

44 (previously presented). Lithographic printing form produced by a process comprising the steps of:

(a) providing a radiation-sensitive element comprising:

- (1) a substrate with at least one hydrophilic surface and
- (2) a radiation-sensitive coating on at least one hydrophilic surface of the substrate, wherein the coating comprises:
  - (i) at least one free-radical polymerizable monomer, oligomer, polymer or mixture thereof with at least one ethylenically unsaturated group each,
  - (ii) at least one photoinitiator or sensitizer, which is capable of absorbing radiation of a wavelength in the range of 250 to 1,200 nm,
  - (iii) at least one stabilizer compound comprising at least one group capable of inhibiting free-radical polymerization, and at least one other group capable of sorption at the hydrophilic surface of the substrate,

wherein the at least one group of the stabilizer compound capable of sorption at the surface of the substrate is:



wherein R<sup>1</sup> is C<sub>1</sub>-C<sub>18</sub> alkyl, C<sub>7</sub>-C<sub>11</sub> aralkyl or C<sub>6</sub>-C<sub>10</sub> aryl and X represents a single bond, -O-, -NH- or -N(C<sub>1</sub>-C<sub>10</sub> alkyl)-, and

- (iv) optionally at least one additive comprising coinitiators which form free radicals after the excitation of the photoinitiator or sensitizer with radiation of a wavelength of 250 to 1,200 nm, binders, dyes, plasticizers, chain transfer agents, leuco dyes, inorganic fillers, surfactants or polymerization inhibitors not suitable for sorption at the surface of the substrate.
- (b) image-wise exposure of the element with radiation of a wavelength adjusted to the absorber contained in the radiation-sensitive coating;
- (c) optionally heating the irradiated element;
- (d) removing the unexposed areas of the coating with an aqueous alkaline developer; and
- (e) optionally heating the developed printing form or subjecting it to overall exposure or both.